Icemos Technology Ltd Product Specification 1003.306503 Issue Date 23 May 2014 15:05:59

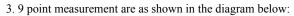
-1		
-1	Part Number	Customer
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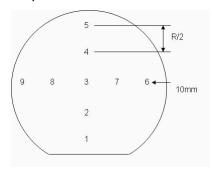
Category		Parameter	Specification	Measurement Method
OverallWafer	1.0	Diameter	150.00 +/- 0.50 mm	WaferVendor
	2.0	Primary Flat Length	57.50 +/- 2.50 mm	Wafer Vendor
	3.0	Primary Flat Orientation	{110}+/- 0.5 degree	Wafer Vendor
	4.0	Growth Method	CZ	Wafer Vendor
	5.0	Туре	Any	Wafer Vendor
	6.0	Dopant	any	Wafer Vendor
	7.0	Resistivity	<0.005 ohm cm	Wafer Vendor
	8.0	Overall Thickness	420.00 +/- 5.00 um	Wafer Vendor
	9.0	Total Thickness Variation (TTV)	<5.00um	Guaranteed by process
	9.1	Bow	<50.00um	ADE measurement
	9.2	Warp	<50.00um	ADE measurement
	10.0	Orientation	<100> +/-0.5	Wafer Vendor
	11.0	Back Surface Quality	Polished with laser mark	Wafer Vendor
	12.0	Front Surface Quality	Prime	Wafer Vendor
	13.0	Edge Chips	None	Bright Light 100% (note 2)
HandleSilicon	14.0	Handle Thickness	420.00 +/- 5.00 um	100% ADE measurement
DeviceSilicon	15.0	Haze	None	Bright Light, 100% (note 2).
	16.0	Scratches	None	Bright Light, 100% (note 2).

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Part Number		Customer	
Category	Parameter	Specification	Measurement Method
Shipping Details	Wafer per box :	Max 25	
	Packaging:	Taped Polypropylene Wafer Box Empak, Ultrapak, 150.00mm Antistatic Double Bagging	
	Lot Shipment Data	Device Thickness Bow / Warp Data Handle and SOI Thickness	
Explanatory Notes	1. Microscope inspec	tion performed using microscope scan as below. 5x objective.	
		pections performed exclude all wafer area outside the edge exclusio	on defined in Overall

Wafer, Edge Exclusion. High intensity bright lamp inspection as per ASTM F523.





Additional Information